



ATOMIC LAYER ETCHING

July 15-17, 2017
Denver, Colorado

4th Int. Atomic Layer Etching Workshop (ALE2017)

Save the Date & Call for Papers

ALE2017 Workshop Overview

The 4th Int. Atomic Layer Etching Workshop (ALE2017) will be held in conjunction with ALD2017 in Denver, Colorado. A broad range of topics are expected including:

- Plasma and/or energy-enhanced ALE
- Gas-phase and/or thermal ALE
- Solution-based including wet ALE
- Atomic layer cleaning (ALC)
- ALE hardware, diagnostics, and instrumentation
- Modeling of ALE
- Integration of ALD + ALE
- Applications for ALE

SUBMIT
Abstract



Deadline: February 17, 2017
www.ald-avs.org

Plenary Speaker

- Richard Gottscho (Lam Research)

Invited Speakers

- Mark Kushner (Univ. Michigan)
- Masanobu Honda (Tel)
- Nathan Marchack (IBM)
- Jesus Del Alamo (MIT)
- Jane Chang (UCLA)
- Stacey Bent (Stanford Univ.)
- Chuck Winter (Wayne State Univ.)
- Younghee Lee (Univ. Colorado)
- Robert Clark (Tel)
- Sumeet Pandey (Micron)
- Nitin Ingle (AMAT)

Program Committee: Steven George (co-Chair) (Univ. Colorado); Keren Kanarik (co-chair) (Lam); Bert Ellingboe (Dublin City Univ.); Sumit Agarwal (Colorado School of Mines); Eric Joseph (IBM); Craig Huffman (Micron); Shahid Rauf (AMAT); Alok Ranjan (TEL); Iqbal Saraf (TEL); Satyarth Suri (Intel); Venkat Pallem (Air Liquide); Jean-Francois de Marneffe (IMEC); Harm Knoop (Oxford Instruments); Fred Roozeboom (TU Eindhoven/TNO); Geun-Young Yeom (Sung Kyun Kwan Univ.); David Coumou (MKS Instruments); Ankur Agarwal (AMAT); Robert Bruce (IBM); Akira Koshiishi (Samsung); David Boris (NRL); Dmitry Suyatin (Lund Univ.)